2017 Fall

"Phase Transformation in Materials"

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Contents for previous class

Interstitial Diffusion / Substitutional Diffusion

3.

- Steady-state diffusion- Fick's First Law
- ➡ Concentration varies with position.
- Non-steady-state diffusion: Fick's Second Law ².
- ➡ Concentration varies with time and position.
 - Atomic Mobility
 - Tracer Diffusion in Binary Alloys
 - High-Diffusivity Paths

1. Diffusion along Grain Boundaries and Free Surface

- 2. Diffusion Along Dislocation
- Diffusion in Multiphase Binary Systems

- 1. Self diffusion in pure material
 - Vacancy diffusion
 - Diffusion in substitutional alloys

Contents for previous class

• **Diffusion** : Movement of atoms to reduce its chemical potential µ. driving force: Reduction of G

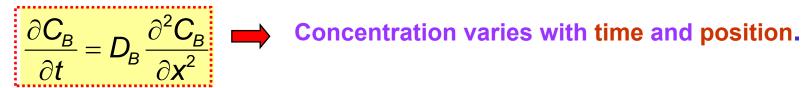
Down-hill diffusion movement of atoms from a high C_B region to low C_B region. **Up-hill diffusion** movement of atoms from a low C_B region to high C_B region.

- Interstitial Diffusion / Substitution Diffusion
 - Steady-state diffusion Fick's First Law_____

$$J_{B} = \frac{1}{6} \Gamma_{B} (n_{1} - n_{2}) = -\left(\frac{1}{6} \Gamma_{B} \alpha^{2}\right) \frac{\partial C_{B}}{\partial x} = -D_{B} \frac{\partial C_{B}}{\partial x}$$

Concentration varies with position. (atoms $m^{-2} s^{-1}$)

- Nonsteady-state diffusion – Fick's Second Law



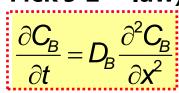
- For random walk in 3 dimensions, after n steps of length α
- **Effect of Temperature on Diffusivity** ٠

$$r = \alpha \sqrt{(\Gamma t)} = f(D) = 2.4\sqrt{Dt}$$
$$\log D = \log D_0 - \frac{Q}{2.3R} \left(\frac{1}{T}\right)^3$$

Solutions to the diffusion equations (Application of Fick's 2nd law)

Ex1. Homogenization

of <u>sinusoidal varying composition</u> in the elimination of segregation in casting



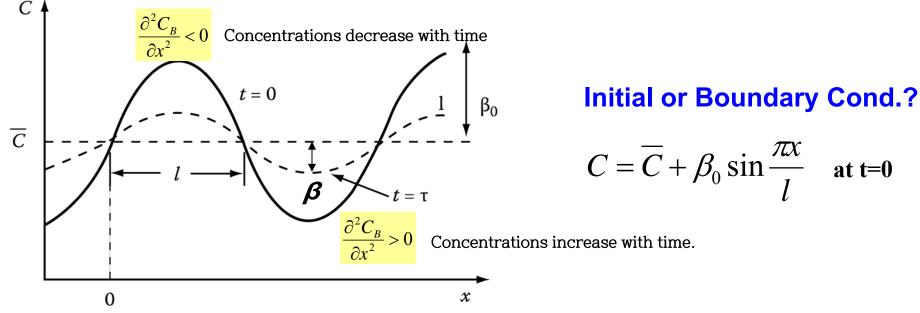


Fig. 2.10 The effect of diffusion on a sinusoidal variation of composition.

C: the mean composition l: half wavelength β_0 : the amplitude of the initial concentration profile

Rigorous solution of $\frac{\partial C}{\partial t} = D \frac{\partial^2 C}{\partial x^2}$ for $C(x,0) = \overline{C} + C$

Using a method of variable separation

Let
$$C = XT \longrightarrow \frac{\partial C}{\partial t} = D \frac{\partial^2 C}{\partial x^2}$$

 $X \frac{dT}{dt} = DT \frac{d^2 X}{dx^2}$
 $\frac{1}{DT} \frac{dT}{dt} = \frac{1}{X} \frac{d^2 X}{dx^2} = -\lambda^2$

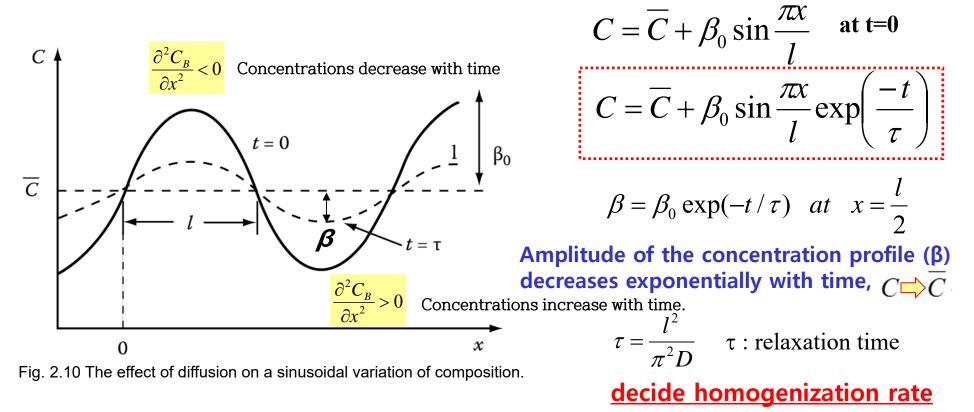
$$\frac{1}{T}\frac{dT}{dt} = -\lambda^2 D$$
$$\frac{d^2 X}{dx^2} + \lambda^2 X = 0$$
$$X = A' \cos \lambda x + B' \sin \lambda x$$
$$T = T_0 e^{-\lambda^2 D t}$$
$$X(x,0) \equiv \overline{C} + \beta_0 \sin \frac{\pi x}{l}$$

or
$$C(x,0) = \overline{C} + \beta_0 \sin \frac{\pi x}{l}$$

 $\therefore C = (A \cos \lambda x + B \sin \lambda x)e^{-\lambda^2 D t}$
 $\therefore C = A_0 + \sum_{n=1}^{\infty} (A_n \sin \lambda_n x + B_n \cos \lambda_n x)$
 $t = 0 \rightarrow C \equiv \overline{C} + \beta_0 \sin \frac{\pi x}{l} \qquad \lambda = \frac{\pi}{l}$
 $; A_0 = \overline{C}, B_n = 0, A_1 = \beta_0$
 $(A_n = 0 \text{ for all others})$
 $\therefore C \equiv \overline{C} + \beta_0 \sin \frac{\pi x}{l} e^{-\frac{t}{2^2/\pi^2 D}}$
 $C = \overline{C} + \beta_0 \sin \frac{\pi x}{l} \exp(-\frac{t}{2^2/\pi^2 D})$
 $\tau = \frac{l^2}{\pi^2 D} \quad \tau : \text{ relaxation time}$
 $\beta = \beta_0 \exp(-t/\tau) \quad at \quad x = \frac{l}{2}$

Solutions to the diffusion equations

Ex1. Homogenization of sinusoidal varying composition in the elimination of segregation in casting



The initial concentration profile will not usually be sinusoidal, but in general any concentration profile can be considered as <u>the sum of an infinite series of sine waves of</u> <u>varying wavelength and amplitude</u>, and each wave decays at a rate determined by jts own " τ ". Thus, the short wavelength terms die away very rapidly and <u>the homogenization</u> <u>will ultimately be determined by τ for the longest wavelength component</u>.

Solutions to the diffusion equations

Ex2. Carburization of Steel

The aim of carburization is to increase the carbon concentration in the surface layers of a steel product in order to achiever a harder wear-resistant surface.

- 1. Holding the steel in CH₄ and/or Co at an austenitic temperature.
- 2. By controlling gases the concentration of C at the surface of the steel can be maintained at a suitable constant value.
- 3. At the same time carbon continually diffuses from the surface into the steel.



Carburizing of steel

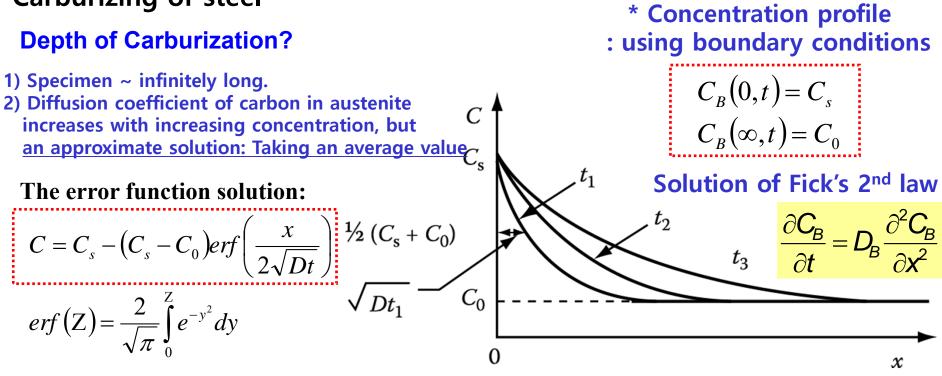


Fig. 2.11 Concentration profiles at successive times $(t_3>t_2>t_1)$ for diffusion into a semi-infinite bar when the surface concentration Cs is maintained constant.

Error function

In mathematics, the error function (also called the Gauss error <u>function</u>) is a non-elementary function which occurs in probability, statistics and partial differential equations.

It is defined as:

$$\mathrm{erf}(x)=\frac{2}{\sqrt{\pi}}\int_{0}^{x}e^{-t^{2}}dt.$$

By expanding the right-hand side in a Taylor series and integrating, one can express it in the form

$$\operatorname{erf}(x) = \frac{2}{\sqrt{\pi}} \sum_{n=0}^{\infty} \frac{(-1)^n x^{2n+1}}{(2n+1)n!} = \frac{2}{\sqrt{\pi}} \left(x - \frac{x^3}{3} + \frac{x^5}{10} - \frac{x^7}{42} + \frac{x^9}{216} - \cdots \right)$$

for every real number x. (From Wikipedia, the free encyclopedia)

Error function

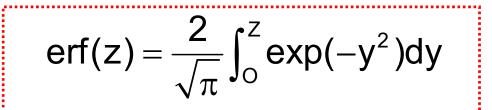
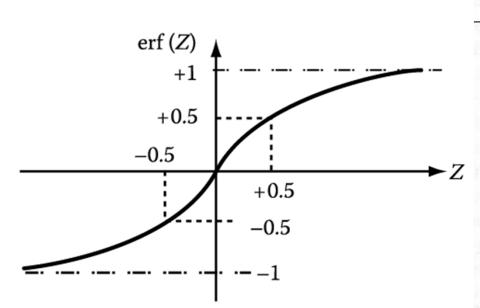


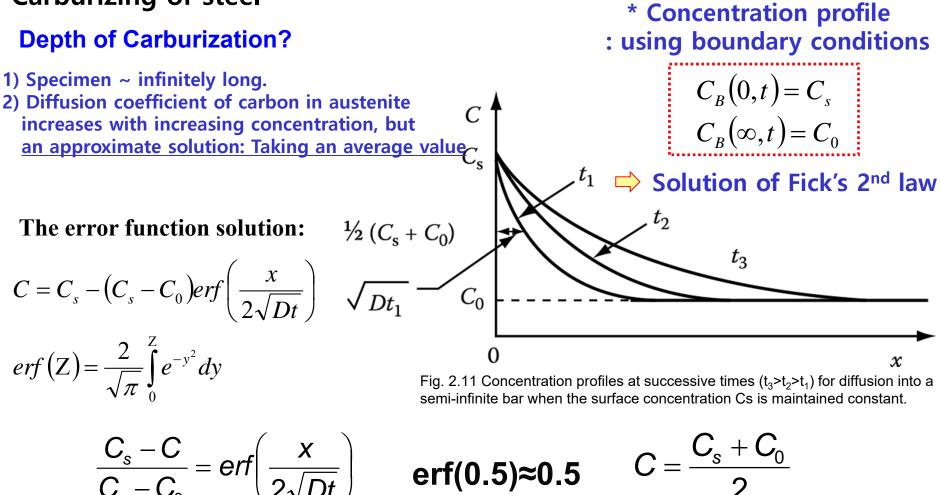
Table 1-1. The Error Function



(a) Schematic diagram illustrating the main features of the error function.

Ζ	$\operatorname{erf}(z)$	Ζ	$\operatorname{erf}(z)$	
0	0	0.85	0.7707	
0.025	0.0282	0.90	0.7969	
0.05	0.0564	0.95	0.8209	
0.10	0.1125	1.0	0.8427	
0.15	0.1680	1.1	0.8802	
0.20	0.2227	1.2	0.9103	
0.25	0.2763	1.3	0.9340	
0.30	0.3286	1.4	0.9523	
0.35	0.3794	1.5	0.9661	
0.40	0.4284	1.6	0.9763	
0.45	0.4755	1.7	0.9838	
0.50	0.5205	1.8	0.9891	
0.55	0.5633	1.9	0.9928	
0.60	0.6039	2.0	0.9953	
0.65	0.6420	2.2	0.9981	
0.70	0.6778	2.4	0.9993	
0.75	0.7112	2.6	0.9998	
0.80	0.7421	2.8	0.9999	

Carburizing of steel



• Since $erf(0.5)\approx 0.5$, the depth at which the carbon concentration is <u>midway between C_s and C_0 is given $(x/2\sqrt{Dt}) \cong 0.5$ </u> that is $x \cong \sqrt{Dt} \rightarrow Depth of Carburization$

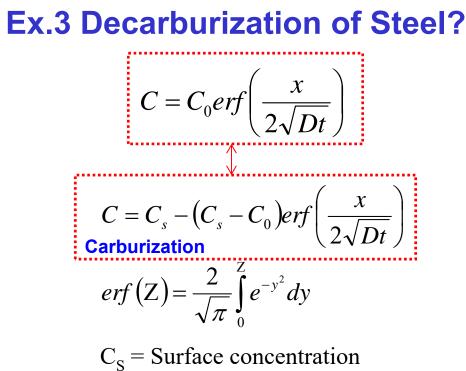
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Carburizing of steel

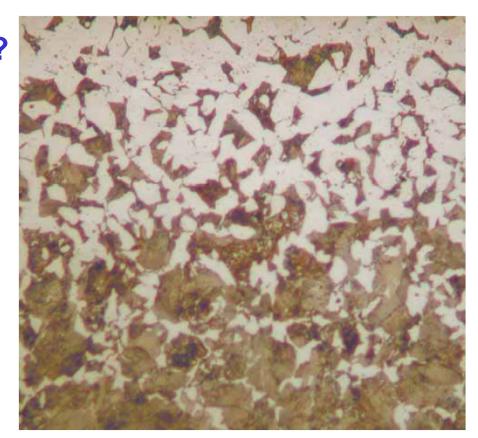
Thus the thickness of the carburized layer is $\cong \sqrt{Dt}$

Note also that the depth of any is concentration line is directly proportion to \sqrt{Dt} , i.e. to obtain a twofold increase in penetration requires a fourfold increase in time.

(2배의 침투 깊이 → 4배의 시간)



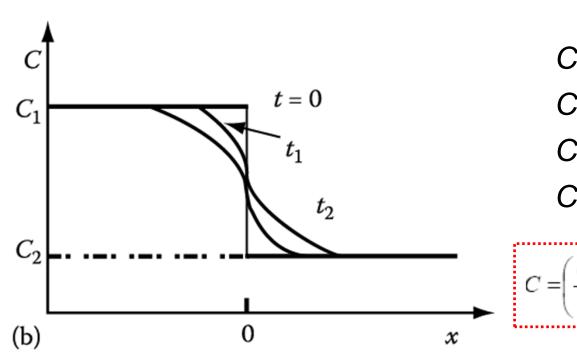
 $C_0 =$ Initial bulk concentration



Solutions to the diffusion equations

Ex4. Diffusion Couple

Joining of two semi-infinite specimens of compositions C_1 and C_2 ($C_1 > C_2$)



Draw C vs. x with time t = 0 and t > 0.

Boundary conditions?

$$C = C_{1} \quad t = 0, \ -\infty < x < 0$$

$$C = C_{2} \quad t = 0, \ 0 < x < \infty$$

$$C = C_{1} \quad x = -\infty, \ 0 < t < \infty$$

$$C = C_{2} \quad x = \infty, \ 0 < t < \infty$$

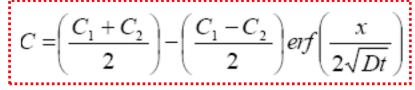


Fig. 2.12 (b) concentration profiles at successive times (t2>t1>0) when two semi-infinite bars of different composition are annealed after welding.

The section is completed with **4 example solutions to Fick's 2nd law:** *carburisation, decarburisation, diffusion across a couple* and *homogenisation.*

The solutions given are as follows:

Process	Solution	
Homogenization	$C = C_{\text{mean}} + \beta_0 \sin\left(\frac{\pi x}{l}\right) \exp\left(-\frac{t}{\tau}\right)$	
	C_{mean} = Mean concentration b_0 = Initial concentration amplitude l = half-wavelength of cells t = relaxation time	
Carburization	$C = C_{\rm S} - (C_{\rm S} - C_0) \operatorname{erf}\left(\frac{x}{2\sqrt{Dt}}\right)$	
	$C_s = Surface concentrationC_0 = Initial bulk concentration$	
Decarburization	$C = C_0 \operatorname{erf}\left(\frac{x}{2\sqrt{Dt}}\right)$ C ₀ = Initial bulk concentration	
Diffusion Couple	$C = \left(\frac{C_1 + C_2}{2}\right) - \left(\frac{C_1 - C_2}{2}\right) \operatorname{erf}\left(\frac{x}{2\sqrt{Dt}}\right)$	
	C_1 = Concentration of steel 1 C_2 = Concentration of steel 2	

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Contents for today's class

Q. Interstitial diffusion vs Substitutional diffusion

- 1. Self diffusion in pure material
- 2. Vacancy diffusion
- **3.** Diffusion in substitutional alloys

Interstitial Diffusion / Substitutional Diffusion

- Diffusion in dilute interstitial alloys ~ relatively simple

because the diffusing atoms are <u>always surrounded by vacant sites</u> to which they can jump whenever they have enough to overcome the energy barrier for migration.

- In substitutional diffusion,

An atom can only jump if there happens to be vacant site at one of the adjacent lattice positions

Probability of vacancy x probability of jump

→ amenable to a simple atomic model: self-diffusion (순금속의 자기확산)

1. Self diffusion in pure material

The rate of self-diffusion can be measured experimentally by introducing a few radioactive A atoms (A*) into pure A and measuring the rate at which penetration occurs at various temperatures. Since A* and A atoms are chemically identical their jump frequencies are almost identical.

Diffusion coefficient

$$D_A^* = D_A = \frac{1}{6} \Gamma_A \alpha^2$$

Assumption : unrelated to the previous jump

most likely to occur back into the same vacancy

 $D_A^* = f D_A$ (f : correlation factor)

close to unity

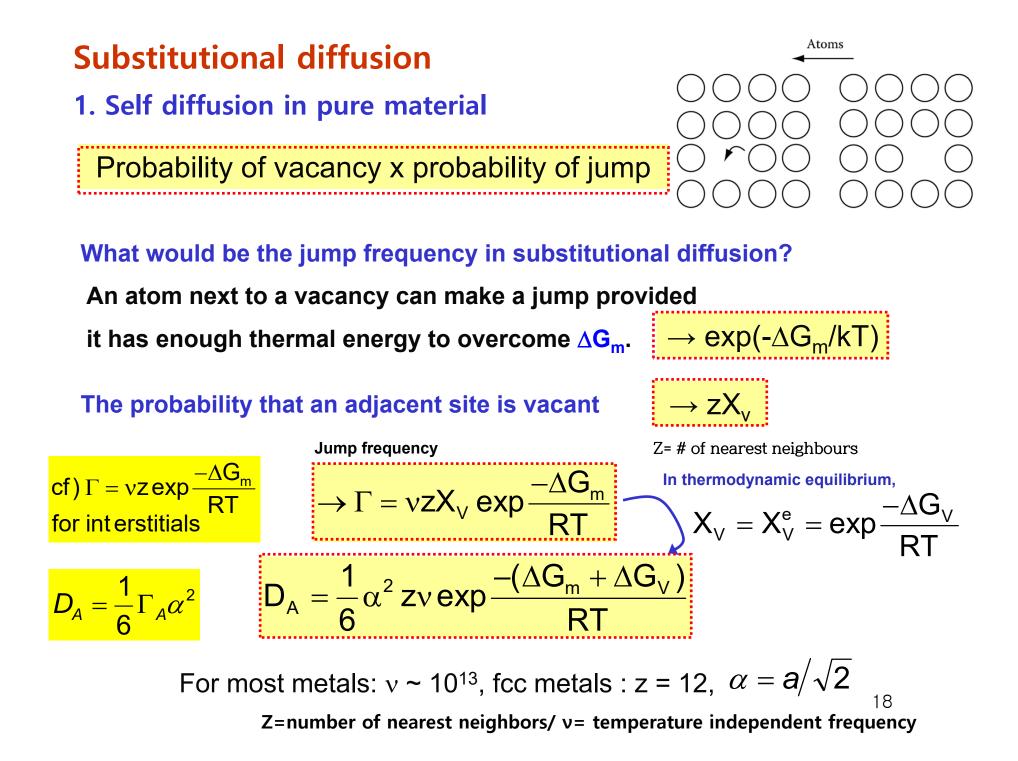
Atoms

The next jump is not equally probable in all directions.

Q. Interstitial diffusion vs Substitutional diffusion

1. Self diffusion in pure material

- 2. Vacancy diffusion
- 3. Diffusion in substitutional alloys



$$D_{A} = \frac{1}{6} \alpha^{2} zv \exp \frac{-(\Delta G_{m} + \Delta G_{V})}{RT} \qquad \Delta G = \Delta H - T\Delta S$$

$$D_{A} = \frac{1}{6} \alpha^{2} zv \exp \frac{\Delta S_{m} + \Delta S_{V}}{R} \exp(-\frac{\Delta H_{m} + \Delta H_{V}}{RT})$$
Z=number of nearest neighbors/ v= temperature independent frequency
For most modulo way 10¹³ for modulo + z = 12, \quad \alpha = \frac{2}{\sqrt{2}}

For most metals:
$$v \sim 10^{10}$$
, icc metals : $z = 12$, $\alpha = \alpha/\sqrt{2}$

$$D_{A} = D_{0} \exp(-\frac{Q_{SD}}{RT}) \qquad D_{0} = \frac{1}{6}\alpha^{2}zv \exp\frac{\Delta S_{m} + \Delta S_{v}}{R}$$
$$Q_{SD} = \Delta H_{m} + \Delta H_{v}$$

Self-diffusion requires the presence of vacancies

~Same with interstitial diffusion except that the activation energy for self-diffusion has an extra term

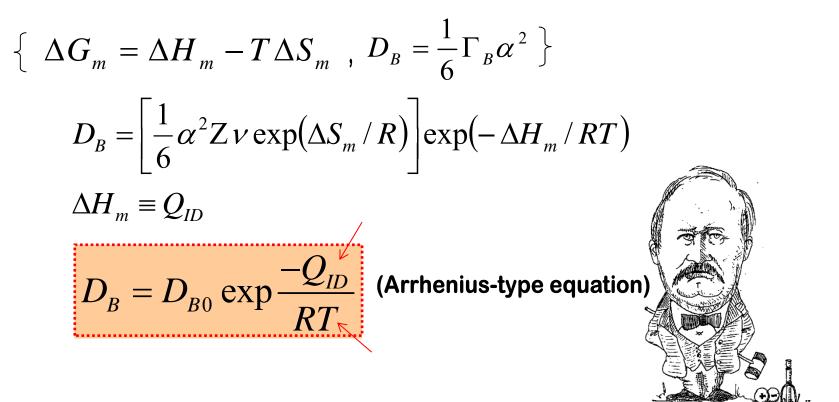
* interstitial diffusion

Thermally activated process jump frequency Γ_B ?

 $\Gamma_B = Z v \exp(-\Delta G_m / RT)$ Z : nearest neighbor sites

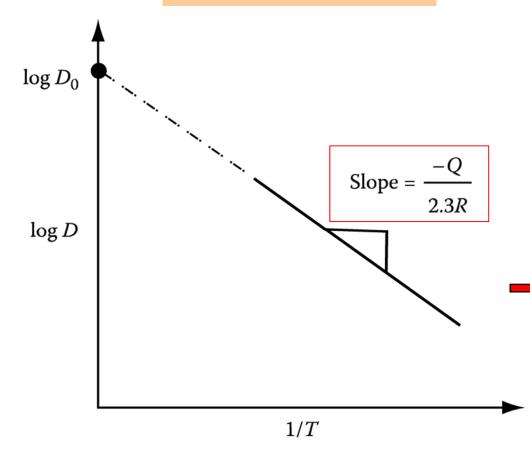
Z : nearest neighbor sites
v : vibration frequency

 $\Delta \boldsymbol{G}_m$: activation energy for moving



Temperature Dependence of Diffusion

$$D_{B} = D_{B0} \exp \frac{-Q_{ID}}{RT}$$



How to determine **Q**_{ID} experimentally?

$$\log D = \log D_0 - \frac{Q}{2.3R} \left(\frac{1}{T}\right)$$

➡ Therefore, from the slope of the D-curve in an log D vs 1/T coordinate, the activation energy may be found.

Fig. 2.7 The slope of log D v. 1/T gives the activation energy for diffusion Q.

Experimental Determination of D

- Deposit a known quantity (M) of a radioactive isotope A*

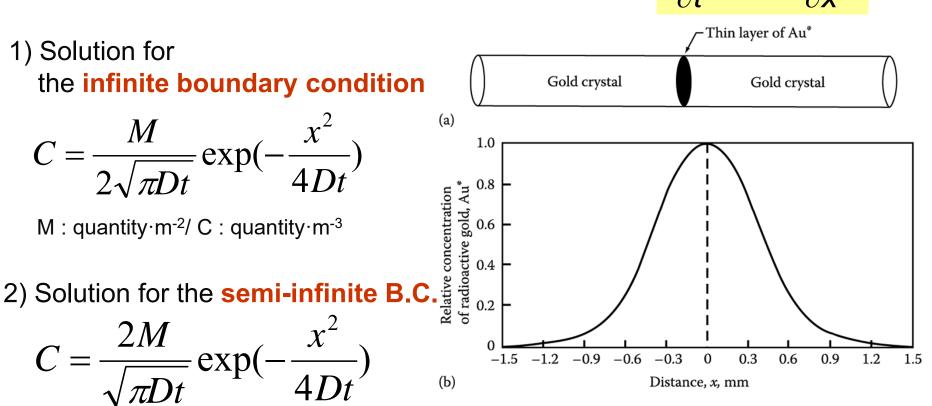


Fig. 2.14 Illustration of the principle of tracer diffusion and of the planar source method for determining the self-diffusion coefficient of gold. (a) Initial diffusion couple with planar source of radioactive gold Au* (b) Distribution of Au* after diffusion for 100h at 920 $^{\circ}$

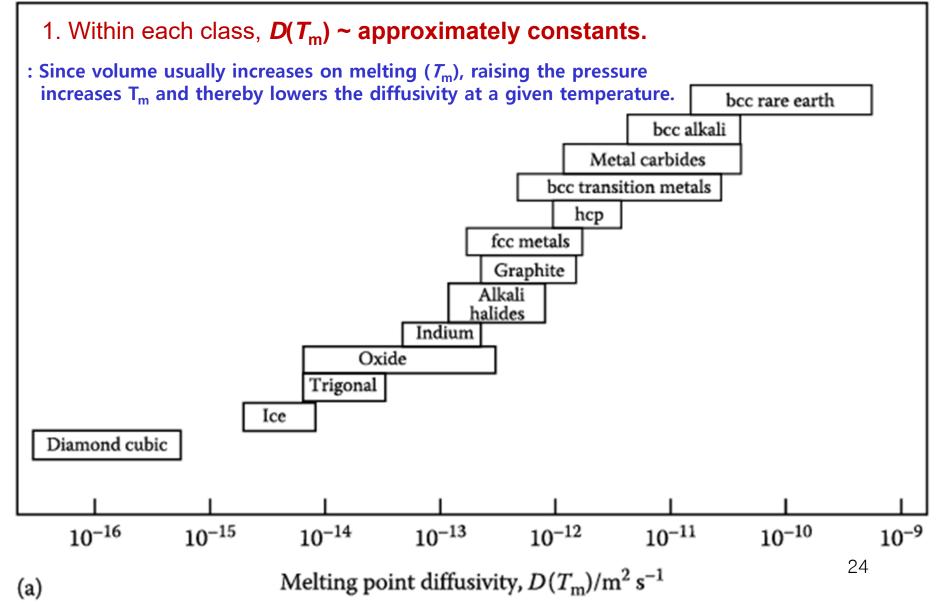
(2.18)

Class	Metal	T _m (K)	D ₀ (mm ² s ⁻¹)	Q (kJ mol ⁻¹)	$\frac{Q}{RT_{m}}$	$Q(T_{\rm m})$ (μ m ² s ⁻¹)	For a given structure and bond type
bcc (rare earths)	ε-Pu	914	0.3	65.7	8.7	53	Q/R <i>T</i> _m is roughly constant;
	δ-Ce	1071	1.2	90.0	10.1	49	
	γ-La	1193	1.3	102.6	10.4	42	\Rightarrow Q is roughly proportional to $T_{\rm m}$.
	γ-Yb	1796	1.2	121.0	8.1	3600	
bcc (alkali metals)	Rb	312	23	39.4	15.2	5.8	
	K	337	31	40.8	14.6	15	
	Na	371	24.2	43.8	14.2	16	Within each class, $D(T_m)$ and D_0
	Li	454	23	55.3	14.7	9.9	· · · · · · · · · · · · · · · · · · ·
bcc (transition metals)	β-T1	577	40	94.6	19.7	0.11	are approximately constants.
Eu	Eu	1095	100	143.5	15.8	14	Most close-packed metals
	Er	1795	451	302.4	20.3	0.71	ex) for fcc and hcp, $Q/RT_m \sim 18$ and
	α-Fe ^a	1811	200	239.7	15.9	26	•••••
	δ-Fe ^a	1811	190	238.5	15.8	26	$D(T_m) \sim 1 \ \mu m^2 s^{-1} \ (10^{-12} \ m^2 s^{-1})$
	β-Τί	1933	109	251.2	15.6	18	
	β-Ζρ	2125	134	273.5	15.5	25	1
	Cr	2130	20	308.6	17.4	0.54	$\log D_0$
	v	2163	28.8	309.2	17.2	0.97	
	Nb	2741	1240	439.6	19.3	5.2	Slope = $\frac{-Q}{-Q}$
	Mo	2890	180	460.6	19.2	0.84	Slope = $\frac{-Q}{2.3R}$
	Ta	3269	124	413.3	15.2	31	log D
	W	3683	4280	641.0	20.9	3.4	
hcp ^a	Cd	594	∥c5	76.2	15.4	0.99	
			⊥c 10	79.9	16.2	0.94	
	Zn	692	∥c 13	91.6	15.9	1.6	
			⊥c 18	96.2	16.7	0.98	
	Mg	922	∥c 100	134.7	17.6	2.3	
			\perp c 150	136.0	17.8	2.9	For a given structure and bond type,
fcc	Pb	601	137	109.1	21.8	0.045	5
	Al	933	170	142.0	18.3	1.9	D(T/T _m) ~ constant
	Ag	1234	40	184.6	18.0	0.61	
	Au	1336	10.7	176.9	15.9	1.3	
	Cu	1356	31	200.3	17.8	0.59	T/T _m : homologous temperature
	Ni	1726	190	279.7	19.5	0.65	23

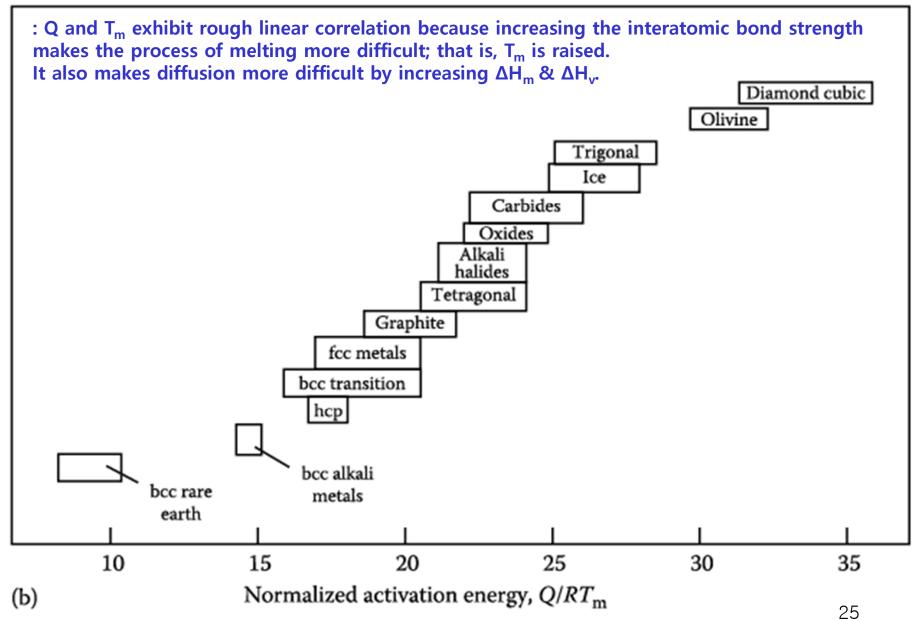
Table 2.2 Experimental Data for Substitutional Self-Diffusionin Pure Metals at Atmospheric Pressure

* Melting point diffusivities for various classes of materials:

: The diffusion coefficients of all materials with a given crystal structure and bond type will be approximately the same at the same fraction of their melting temperature, i.e. $D(T/T_m) = \text{const.}$



For a given structure and bond type, Q/RT_m is roughly constant;

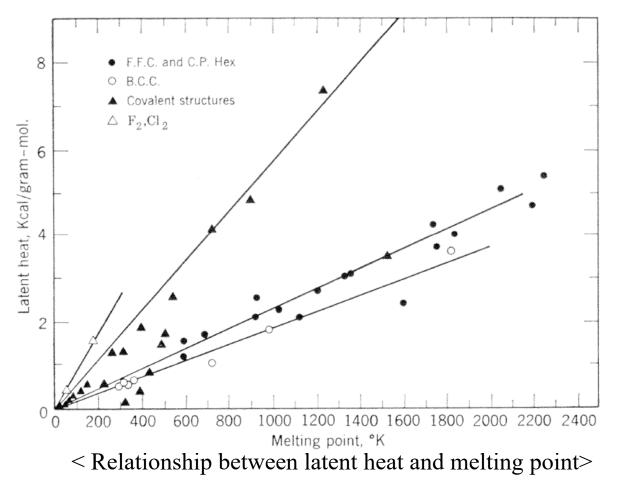


$$\frac{L}{RT_E} = \ln \frac{A_M}{A_F}$$
 b) $A_M \sim 1$ for all liquid, A_F depends on crystal structure

- Metallic structure (FCC, C.P.H, and BCC, "less localized bonding") ~ good relationship compared with the structures which are covalently bonded ("specific directional bonds").

- Molecular liquid such as F_2 , $Cl_2 \sim extra \ condition \ for A_F$

(... molecule must be correctly oriented in order to be accommodated.)



Consider the effect of temperature on self-diffusion in Cu:

ex) At 800°C, D_{Cu} = 5 × 10⁻⁹ mm²s⁻¹, α = 0.25 nm Γ_{Cu} : ?

$$D_{B} = \frac{1}{6} \Gamma_{B} \alpha^{2} \qquad \Gamma_{Cu} = 5 \times 10^{5} \text{ jumps s}^{-1}$$

After an hour, diffusion distance (x)? $\sqrt{Dt} \sim 4 \mu$ How do we determine D_{Cu} at low temperature such as 20°C? $\log D$

Hint) From the data in Table 2.2, how do we estimate D_{Cu} at 20°C?

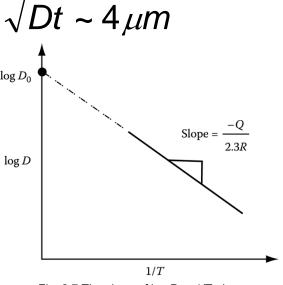


Fig. 2.7 The slope of log D v. 1/T gives the activation energy for diffusion Q.

At 20°C, $D_{Cu} \sim 10^{-34} \text{ mm}^2 \text{s}^{-1}$ $\Gamma_{Cu} \sim 10^{-20} \text{ jumps s}^{-1}$

 \rightarrow Each atom would make one jump every 10¹² years!

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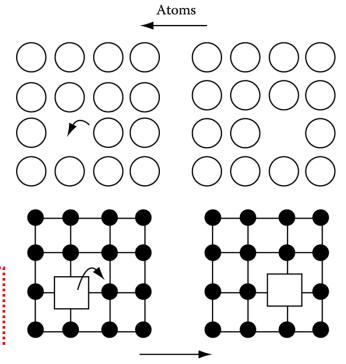
Q. Interstitial diffusion vs Substitutional diffusion

- 1. Self diffusion in pure material
- 2. Vacancy diffusion
- **3.** Diffusion in substitutional alloys

2. Vacancy diffusion

All the surrounding atoms are possible jump sites of a vacancy, which is analogous to interstitial diffusion.

$$D_{v} = \frac{1}{6} \alpha^{2} \Gamma_{v}$$
$$= \frac{1}{6} \alpha^{2} z v \exp(\Delta S_{m} / R) \exp(-\Delta H_{m} / RT)$$



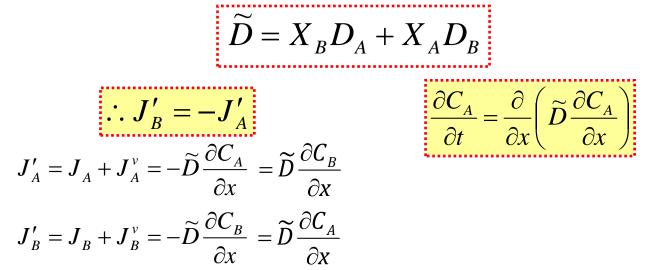
Vacancies

Comparing D_v with the self-diffusion coefficient of A, D_A ,

$$D_v = D_A / X_v^e$$

This shows in fact that the diffusivity of vacancy (D_v) is many orders of magnitude greater than the diffusivity of substitutional atoms (D_A). 29

Q: Diffusion in substitutional alloys?



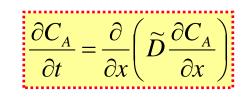
Fick's 1st law for substitutional alloy Fick's 2nd law for substitutional alloy

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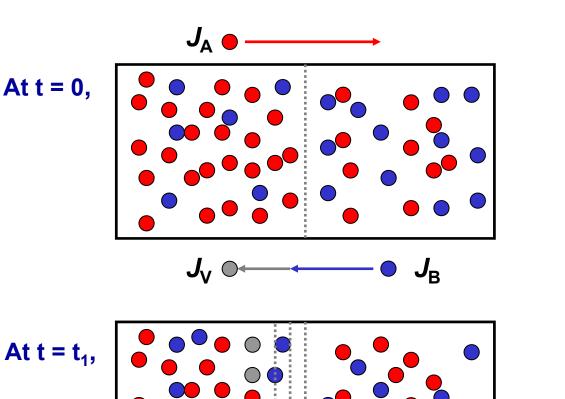
3. Diffusion in substitutional alloys

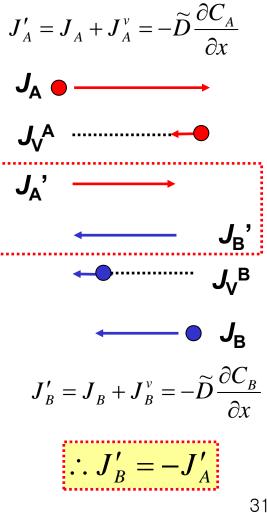
* During self-diffusion, all atoms are chemically identical. : probability of finding a vacancy and jumping into the vacancy ~ equal

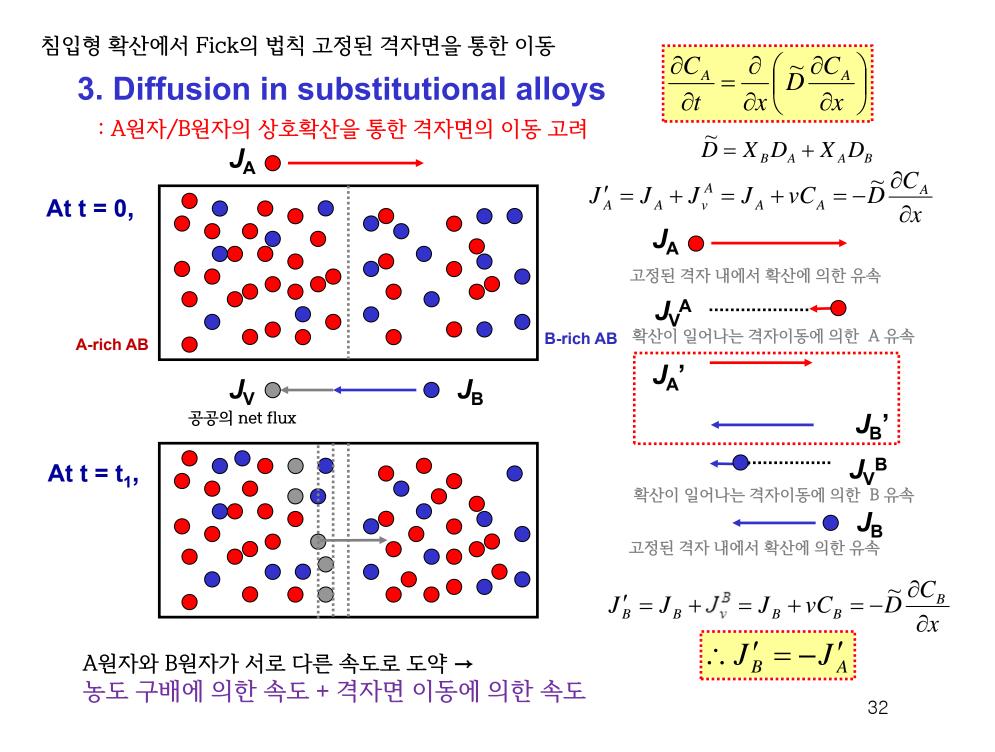
* In binary substitutional alloys, each atomic species must be given its own intrinsic diffusion coefficient D_A or D_B .



 $\widetilde{D} = X_{R}D_{A} + X_{A}D_{R}$

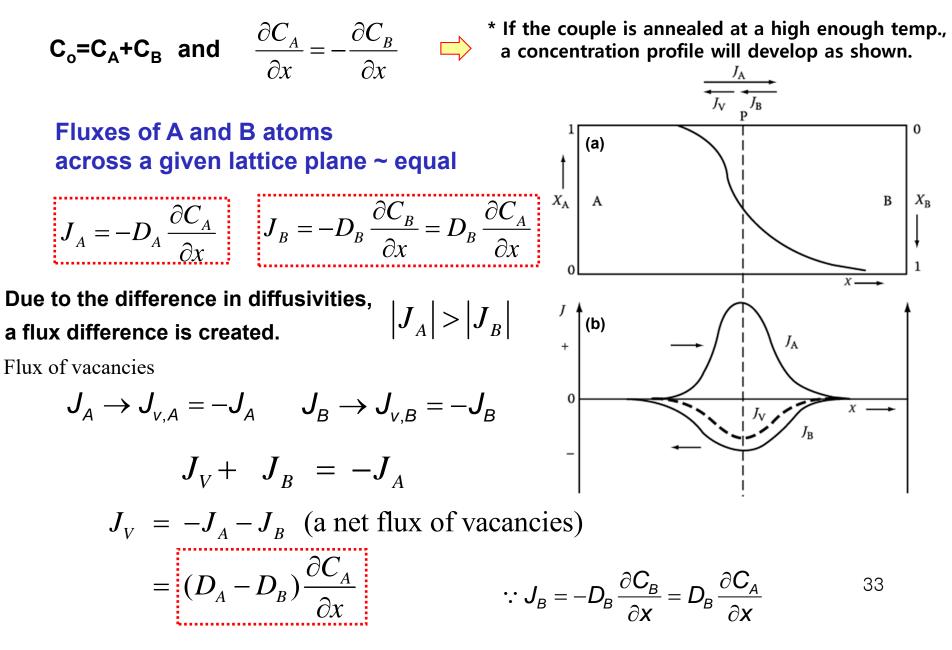






1) INTERDIFFUSION

Assume that C_0 : total number of atoms (A, B) per unit volume = constant, independent of composition



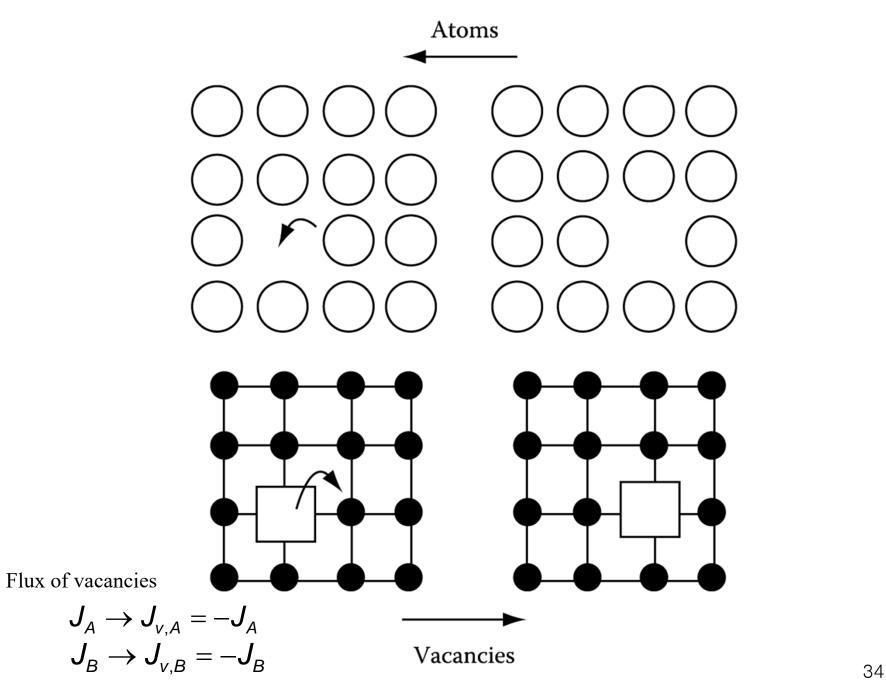
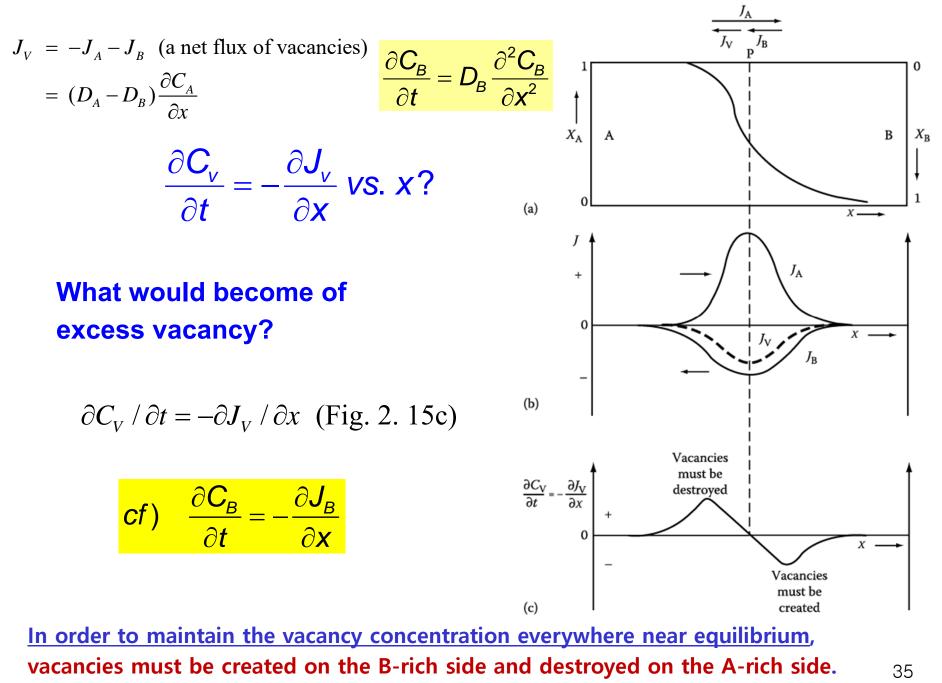


Fig. 2.16 The jumping of atoms in one direction can be considered as the jumping of vacancies in the other direction.



* Net flux of vacancies across the middle of the diffusion couple \rightarrow "Movement of lattice"

Kirkendall effect

Creation/destruction of vacancies is accomplished by *dislocation climb*.

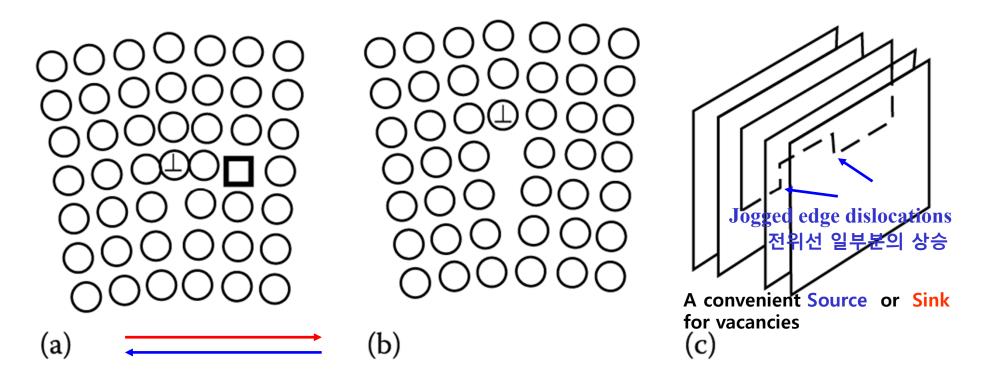


Fig. 2.17 (a) before, (b) after: <u>a vacancy is absorbed at a jog on an edge dislocation</u> (positive climb). (b) before, (a) after: <u>a vacancy is created by negative climb of an edge dislocation</u>. (c) Perspective drawing of a jogged edge dislocation.

If dislocation climbs continue to occur, what would happen? ³⁶

3.3.1 Low-Angle and High-Angle Boundaries

Low-Angle Boundaries

Symmetrical low-angle tilt boundary

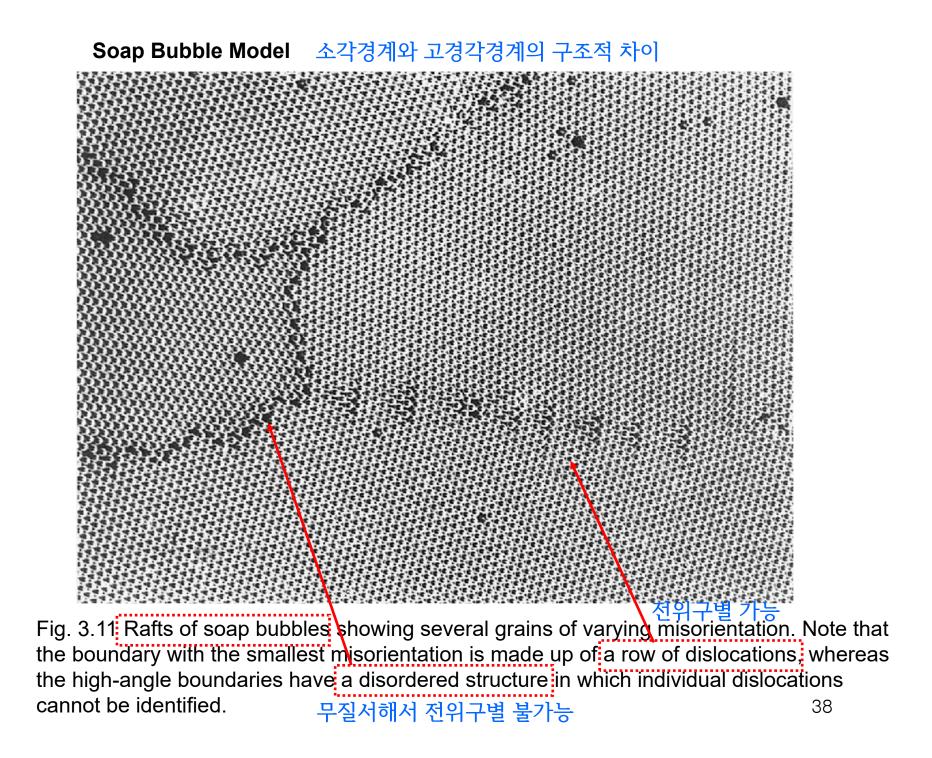
θ Grain- $D = \frac{b}{\theta}$ boundary transition zone \rightarrow Broken Bonds (a)

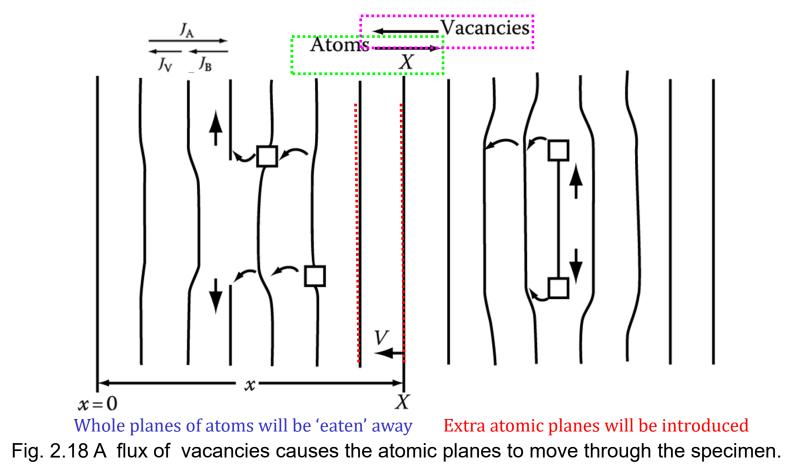
Fig. 3.7 (a) Low-angle tilt boundary

An array of parallel edge dislocations

Fig. 3.10 Disordered grain boundary structure (schematic).

High Angle Grain Boundary





2) velocity of the movement of the lattice plane is related to the net flux of vacancies across the middle of the diffusion couple, such that

$$\begin{array}{c} Av \cdot \delta t \cdot C_{0} = J_{v}A \cdot \delta t \longrightarrow J_{v} = C_{0}v \\ \text{# of removed atoms} & \text{# of vacancies} \\ \text{crossing the plane} & v = \frac{1}{C_{0}} \left(D_{A} - D_{B} \right) \frac{\partial C_{A}}{\partial x} = (D_{A} - D_{B}) \frac{\partial X_{A}}{\partial x} \\ \end{array}$$

X_A: mole fraction of A atoms, *v*: marker velocity (velocity of the lattice plane)

In practice, internal movement of lattice planes are usually not directly of interest. More practical questions concern how long homogenization of an alloy takes, or how rapidly the composition will change at a fixed position relative to the ends of a specimen. (균질화 시간 혹은 확산쌍의 위치에 따른 조성 변화)

Derivation of the Fick's 2nd law for substitutional alloys

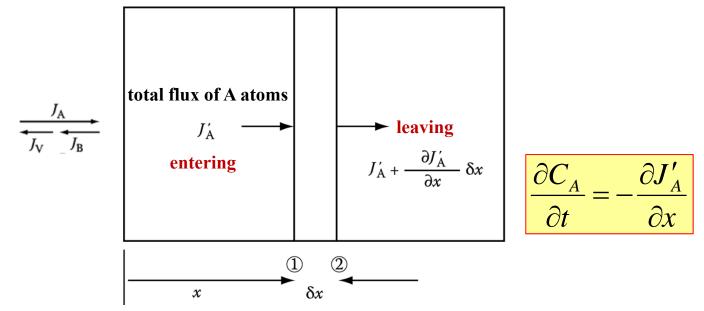
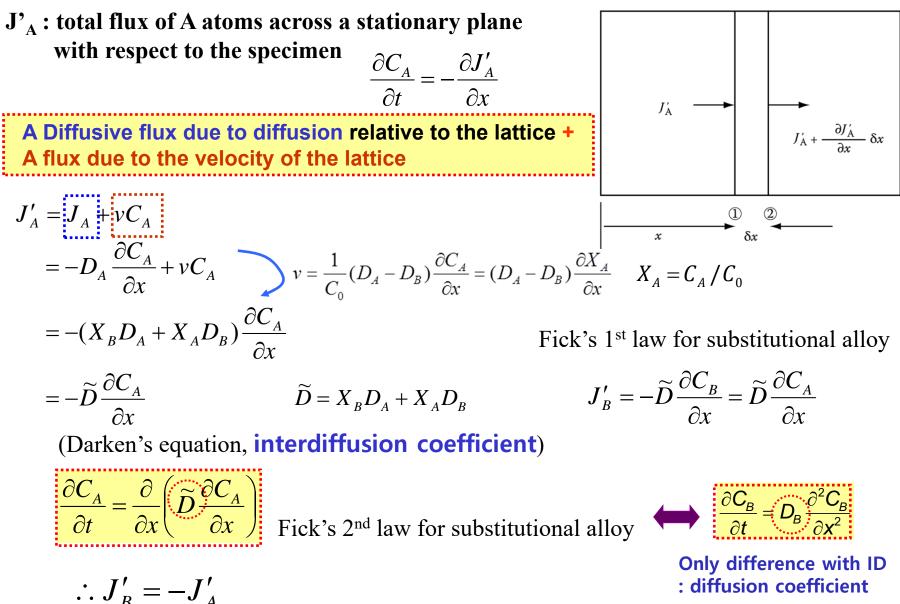


Fig. 2.19 Derivation of Fick's second law for interdiffusion. (See text for details.)

J'_A : total flux of A atoms across a stationary plane with respect to the specimen

3) Derivation of the Fick's 2nd law for substitutional alloys



Q: How can we determine *D*_A and *D*_B? in substitutional alloys?

By measuring velocity of a lattice (v) and interdiffusion coefficient (\tilde{D})

$$\mathbf{v} = (D_A - D_B) \frac{\partial X_A}{\partial x} = (D_B - D_A) \frac{\partial X_B}{\partial x} \qquad \Longrightarrow \quad \widetilde{D} = X_B D_A + X_A D_B$$

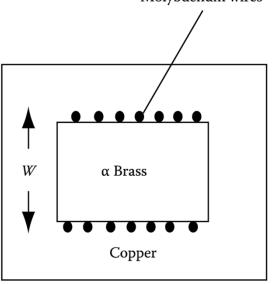
The interdiffusion coefficient (\tilde{D}) can be experimentally measured by determining the variation of X_A and X_B after annealing a diffusion couple.

How can we determine D_A and D_B ?

$$\mathbf{v} = (D_A - D_B) \frac{\partial X_A}{\partial x} = (D_B - D_A) \frac{\partial X_B}{\partial x}$$
$$\implies \widetilde{D} = X_B D_A + X_A D_B$$

When the velocity of a lattice (v) and interdiffusion coefficient (\tilde{D}) are known, D_A and D_B for the composition at the markers can be calculated.

How can we determine the velocity of a lattice (v)?



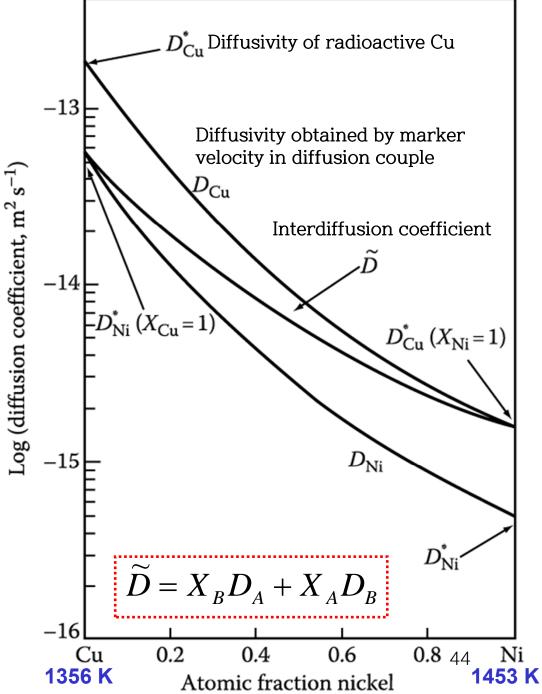
The displacement of wires during diffusion was first observed by Smigelskas and Kirkendall in 1947 and is usually known as the Kirkendall effect.

$D_{Zn} > D_{Cu}$

After annealing at a high temperature, it was found that the separation of the markers (w) had decreased.43 The relationship between the various diffusion coefficients in the Cu-Ni system at 1273 K.

Atoms with the lower melting point possess a higher D.

 D_{Cu} , D_{Ni} , (\tilde{D}) are all composition dependent, increasing as X_{Cu} increases.



• In concentrated alloys, the experimentally determined values of \tilde{D} , D_A and D_B are also found to show the same form of temperature dependence.

$$\widetilde{D} = \widetilde{D}_0 \exp(-Q/RT)$$

Variation of \tilde{D} with composition:

- For a given crystal structure, \tilde{D} at T_m is roughly constant. Therefore if adding B to A decreases T_m , \tilde{D} will increase at a given temperature, and vice verse.

Ex) diffusion of carbon in Fe at 1183 K, $D_C^{\alpha} / D_C^{\gamma} \sim 100$

Self-diffusion coefficients for Fe at 1133 K, $D_{Fe}^{\alpha} / D_{Fe}^{\gamma} \sim 100$

BCC_more open and less lattice distortion

4) Diffusion in dilute substitutional alloy

$$\widetilde{D} = X_B D_A + X_A D_B$$

(interdiffusion coefficient)

For Dilute Substitutional Alloys

if $X_A \approx 1$, $\tilde{D} = D_R$

The rate of homogenization in dilute alloys is controlled by how fast the solute (B) atoms can diffuse.

In this case, D_B is called <u>'impurity diffusion coefficient'</u>. ~ can be measured by using radioactive tracers like self-diffusion

* D_{B} in a dilute solution of B in A is greater than D_{A} .

- The reason for this is that the <u>solute atoms can attract vacancies</u> so that there is more than a random probability of finding <u>a vacancy next</u> to a solute atom with the result that they can <u>diffuse faster than solvent</u>.
- This is caused by the larger size or higher valency of the B atoms compared to those of A atoms.
- If the binding energy is very large, the vacancy will be unable to estape from the solute atom. In this case the <u>solute-vacancy pair can diffuse</u> <u>through the lattice together.</u>

The relationship between D_{Cu}^* Diffusivity of radioactive Cu the various diffusion coefficients in the Cu-Ni system at 1273 K. -13 Atoms with the lower melting point Diffusivity obtained by marker possess a higher D. velocity in diffusion couple Log (diffusion coefficient, $m^2 s^{-1}$) D_{Cu} D_{Cu} , D_{Ni} , (\tilde{D}) are all composition Interdiffusion coefficient dependent, increasing as X_{cu} increases. -14 $= D_{\rm Ni}^* (X_{\rm Cu} = 1)$ * Concentration of A & B at any x after t $D_{Cu}^{*}(X_{Ni}=1)$ -Impurity $\frac{\partial C_A}{\partial t} = \frac{\partial}{\partial x} \left(\widetilde{D} \frac{\partial C_A}{\partial x} \right) \quad \text{Eq. (2.53)}$ diffusion coefficient $D_{\rm Ni}$ -15 \Rightarrow By solving (2.53) with appropriate BCs, 1500 Liquid 1455* \rightarrow Possible to obtain C_A (x, t) and C_B (x,t) Liquidus lir 1300 Characteristic relaxation time for an Homogenization anneal 1200 $\tau = \frac{l^2}{\pi^2 \tilde{D}}$ τ : relaxation time 1100 1085° C -160.4 0.8 (The range of composition is small enough that Cu 0.2 0.6 any effect of composition on $\tilde{\rho}$ can be ignored) Atomic fraction nickel

1356 K

 D_{N}

Ni

1453 K

Contents for today's class

- Substitution Diffusion
 - 1. Self diffusion in pure material (by radioactive element)

Probability of vacancy x probability of jump

$$D_{A} = \frac{1}{6} \alpha^{2} zv \exp \frac{-(\Delta G_{m} + \Delta G_{v})}{RT}$$

$$D_{A} = D_{0} \exp(-\frac{Q_{SD}}{RT})$$

$$Q_{SD} = \Delta H_{m} + \Delta H_{v}$$
2. Vacancy diffusion

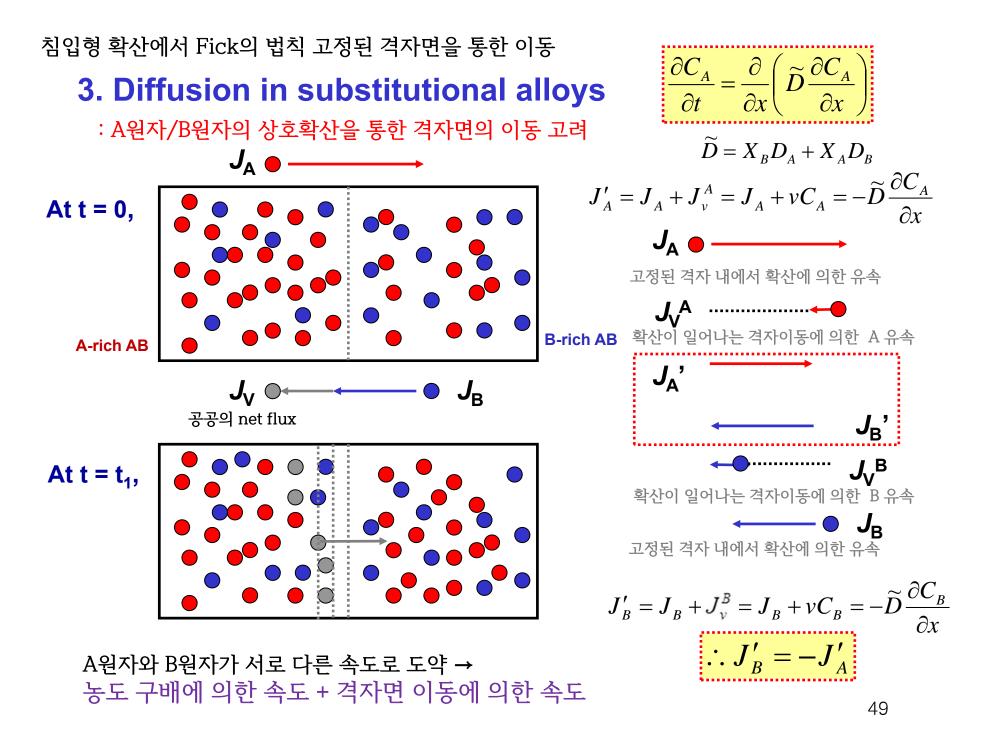
$$Q_{SD} = \Delta H_{m} + \Delta H_{v}$$

$$D_{v} = \frac{1}{6} \alpha^{2} zv \exp(\Delta S_{m} / R) \exp(-\Delta H_{m} / RT)$$
Comparing D_v with the self-diffusion coefficient of A, D_A

$$D_{v} = D_{A} / X_{v}^{e}$$

 $X_V = X_V^e = exp \frac{-\Delta G_V}{RT}$

3. Diffusion in substitutional alloys



The relationship between D_{Cu}^* Diffusivity of radioactive Cu the various diffusion coefficients in the Cu-Ni system at 1273 K. -13 Atoms with the lower melting point Diffusivity obtained by marker possess a higher D. velocity in diffusion couple Log (diffusion coefficient, $m^2 s^{-1}$) D_{Cu} D_{Cu} , D_{Ni} , (\tilde{D}) are all composition Interdiffusion coefficient dependent, increasing as X_{cu} increases. -14 $= D_{\rm Ni}^* (X_{\rm Cu} = 1)$ * Concentration of A & B at any x after t $D_{Cu}^{*}(X_{Ni}=1)$ -Impurity $\frac{\partial C_A}{\partial t} = \frac{\partial}{\partial x} \left(\widetilde{D} \frac{\partial C_A}{\partial x} \right) \quad \text{Eq. (2.53)}$ diffusion coefficient $D_{\rm Ni}$ -15 \Rightarrow By solving (2.53) with appropriate BCs, 1500 Liquid 1455* \rightarrow Possible to obtain C_A (x, t) and C_B (x,t) Liquidus lir 1300 Characteristic relaxation time for an Homogenization anneal 1200 $\tau = \frac{l^2}{\pi^2 \tilde{D}}$ τ : relaxation time 1100 1085° C -160.4 0.8 (The range of composition is small enough that Cu 0.2 0.6 any effect of composition on $\tilde{\rho}$ can be ignored) 1356 K Atomic fraction nickel

 D_{N}

Ni

1453 K